



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Seiichiro TACHIBANA et al.

Confirmation No.: 3891

Serial No.: 10/611,853

Examiner: PEZZUTO, Helen Lee

Filed: July 3, 2003

Group Art Unit: 1713

Title: ETHER, POLYMER RESIST COMPOSITION AND PATTERNING PROCESS

COMMENTS ON EXAMINER'S REASONS FOR ALLOWANCE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Applicants acknowledge the Notice of Allowability mailed March 16, 2004. With respect to the Examiner's Statement of Reasons for Allowance at paragraph 2 of the Notice of Allowability, Applicants respectfully submit that the ether monomeric units (1-1) or (1-2) are optionally derived from an ether compound (1).

The Commissioner is hereby authorized to charge any fees associated with this response or credit any overpayment to Deposit Account No. 13-3402.

Respectfully submitted,

James E. Buland, Reg. No. 37,432
Attorney for Applicants

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Attorney Docket No.: KOJIM-445 D1

Date: May 19, 2004

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